

# Dan N Le

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/9883206/publications.pdf>

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7  
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2258059

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#	ARTICLE	IF	CITATIONS
1	Low Temperature Thermal Atomic Layer Deposition of Aluminum Nitride Using Hydrazine as the Nitrogen Source. <i>Materials</i> , 2020, 13, 3387.	2.9	12
2	Plasma-Enhanced Atomic-Layer Deposition of Nanometer-Thick SiN <sub>x</sub> Films Using Trichlorosilane for Etch-Resistant Coatings. <i>ACS Applied Nano Materials</i> , 2021, 4, 2558-2564.	5.0	8
3	A Novel Combinatorial Approach to the Ferroelectric Properties in Hf <sub>x</sub> Zr <sub>1-x</sub> O <sub>2</sub> Deposited by Atomic Layer Deposition. <i>Physica Status Solidi - Rapid Research Letters</i> , 2021, 15, 2100053.	2.4	3
4	Relaxation Induced by Imprint Phenomena in Low-Temperature (400 °C) Processed Hf <sub>0.5</sub> Zr <sub>0.5</sub> O <sub>2</sub> -Based Metal-Ferroelectric-Metal Capacitors. <i>ACS Applied Electronic Materials</i> , 2022, 4, 1405-1414.	4.3	2
5	Highly Reliable Selection Behavior With Controlled Ag Doping of Nano-Polycrystalline ZnO Layer for 3D X-Point Framework. <i>IEEE Electron Device Letters</i> , 2022, 43, 21-24.	3.9	1
6	Nano-polycrystalline Ag-doped ZnO layer for steep-slope threshold switching selectors. <i>AIP Advances</i> , 2021, 11, 115213.	1.3	0
7	High wet-etch resistance SiO <sub>2</sub> films deposited by plasma-enhanced atomic layer deposition with 1,1,1-tris(dimethylamino)disilane. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2022, 40, 022406.	2.1	0